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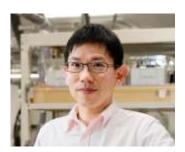
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Shih-Nan Hsiao received a Ph.D degree in materials science and engineering from the Feng Chia University, Taichung, Taiwan. In 2010, he was a visiting scholar at the Argonne National Laboratory, USA, focusing on microbeam x-ray diffraction. From 2011 to 2014, he worked at the National Synchrotron Radiation Research Center as a postdoctoral fellow, conducting research on magnetic materials using a variety of x-ray based techniques. Following his Postdoctoral, he spent 3 years at industry area, where he worked on surface treatment, coating and finishing using arc ion plating, high-power impulse magnetron sputtering, and others. He is currently a professor at the Center for Low temperature Plasma Sciences, Nagoya university, Japan. His research interests include cryogenic plasma etching, atomic layer etching, plasma diagnostics and simulations for semiconductor processes. He has severed as a Guest Editor in MDPI Journal: Coating for two years. He is now an Editor for the Elsevier Journal: Material Chemistry and Physics.